

Ion Implanter line-up

We can perform ion implantation processing under various conditions according to customer requirements, with a wide variety of samples from chips to 12-inch wafers. The implantation conditions range from 10 to 8,000 keV, from room temperature to high temperature heating (600 ° C), and about 60 types of ionic species can be handled.

Ion implanter

200 keV implanter



400 keV implanter



Ion implanter

250 keV implanter



8 MeV implanter

